

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

INFORMATION DISCLOSURE CITATION <i>(use several sheets if necessary)</i>				ATTY DOCKET NO. 2004US301	SERIAL NO. 10/808,884		
				Yu SUI et al.			
				FILING March 25, 2004	GROUP 1756		
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL	TRADE NAME	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
KAD		4,845,265	7/4/1989	Lapin et al.	560	84	
KAD		5,939,235	8/17/1999	Kondo et al.	430	270.1	
KAD		5,972,560	10/26/1999	Kaneko et al	430	270.1	
KAD		6,124,077	9/26/2000	Imai et al.	430	281.1	
KAD		6,187,509 B1	2/13/2001	Imai et al.	430	284.1	
KAD		6,846,612 B2	1/25/2005	Deshpande	430	271.1	
KAD		US 2002/0045130 A1	4/18/2002	Nitta et al.	430	288.1	
KAD		US 2003/0162120 A1	8/28/2003	Yoon et al.	430	156	
FOREIGN PATENT DOCUMENTS							
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
KAD	JP 6-295064 A	10/21/1994	JAPAN			✓	<i>English abstract only</i>
OTHER DOCUMENTS <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>							
KAD			English Language Abstract of JP 6-295064 A.				
KAD			Houlihan et al., "Chemically Amplified Resists: The Chemistry and Lithographic Characteristics of Nitrobenzyl Benzenesulfonate Derivatives", Journal of Photopolymer Science and Technology, Vol. 1, No. 3, pp. 259 - pp. 273 (1990)				
EXAMINER <i>K-Duda</i>				DATE CONSIDERED <i>7/23/07</i>			
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INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i>		Docket Number (Optional) 2004US301	Application Number 10/808,884
		Applicant(s) Yu Sui et al.	
		Filing Date 3/25/04	Group Art Unit 1756
EXAMINER INITIAL	OTHER DOCUMENTS <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>		
VAD	Lee et al., "Performance of vinyl ether cross-linkers on resist for 193 nm lithography", SPIE, Vol. 4690, pp. 541 - 548 (2002)		
VAD	Moon et al., "Three-component photoresists based on thermal crosslinking and acidolytic cleavage", Polymer 41, pp. 4013 - pp. 4019 (2000)		
VAD	Nakano et al., "Positive-Type Photopolyimide Based on Vinyl Ether Crosslinking and De-Crosslinking", Journal of Photopolymer Science and Technology Vol. 13, No. 5, pp. 715 - pp. 718 (2000)		
VAD	Noppakunkilograt et al., "Visible Light-Sensitive Positive-Working Photopolymer Based on Poly(p-hydroxystyrene) and Vinyl Ether Crosslinker", Journal of Photopolymer Science and Technology Vol. 13, No. 5, pp. 719 - pp. 722 (2000)		
VAD	Schacht et al., "Acid Labile Cross-Linked Units: A Concept for Improved Positive Deep-UV Photoresists", American Chemical Society, pp. 78 - pp. 94 (1998)		
VAD	White et al., "Synthesis and characterization of photodefinable polycarbonates for use as sacrificial materials in the fabrication of microfluidic devices", SPIE Vol. 4690, pp. 242 - pp. 253 (2002)		
VAD	Yamada et al., "The design and study of aqueous-processable positive tone photoresists", SPIE Vol. 3999, pp. 569 - pp. 578 (2000)		
VAD	Yamada et al., "Positive and Negative Tone Water Processable Photoresists: A Progress Report", SPIE Vol. 3333, pp. 245 - pp. 253 (2000)		
VAD	Yamaoka et al., "Reaction of vinyl ethers and application of photoreactive process", Trends in Photochemistry & Photobiology Vol. 7, pp. 47 - pp. 70 (2001)		
VAD	Editor Leonard V. Interrante, Chemistry of Materials, Vol. 6, No. 10 (1994), pp. 1A - 6A.		
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